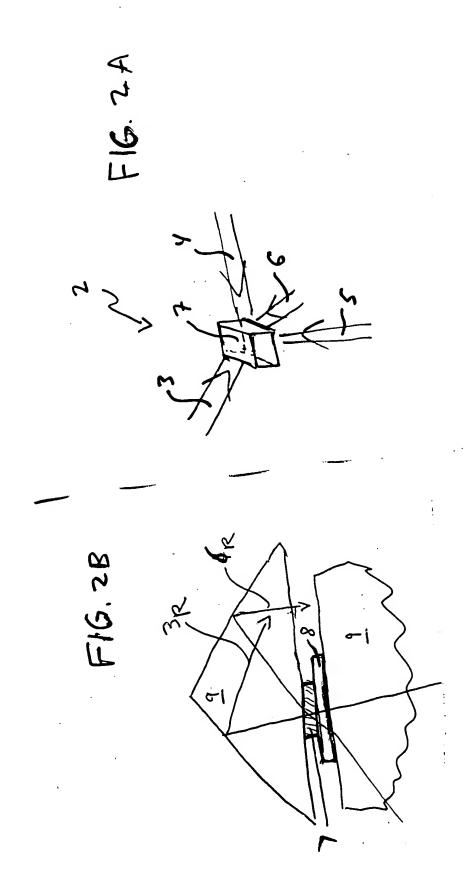
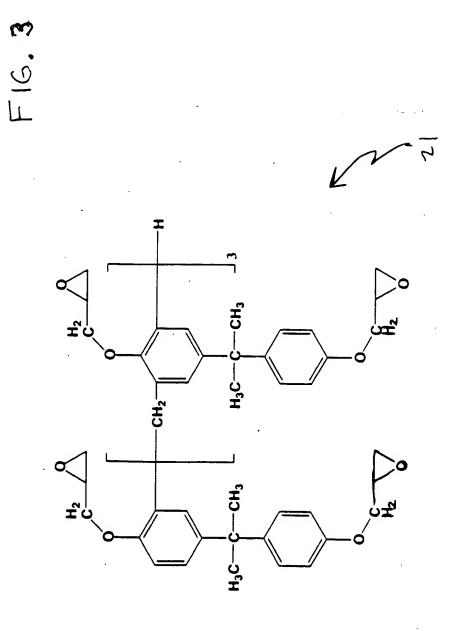
Provide photo-sensitive medium
Liz
Expose the medium to an intensity pattern under conditions that inhibit refractive inde
conditions that inhibit refractive index changes
L14
Heat the exposed medium to favorize refractive index characters on the
refractive index changing reactions
LI
16
wash the cured medium to remove
either reacted or unrocated at
either reacted or unreacted portions of the medium
-18
Dry the washed medium under conditions that limit internal stresses
conditions that limit internal at
CZO
<u> </u>
10
F16. 1





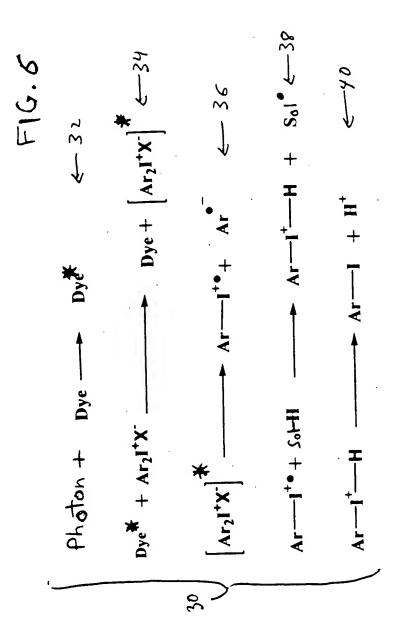
F16.4A

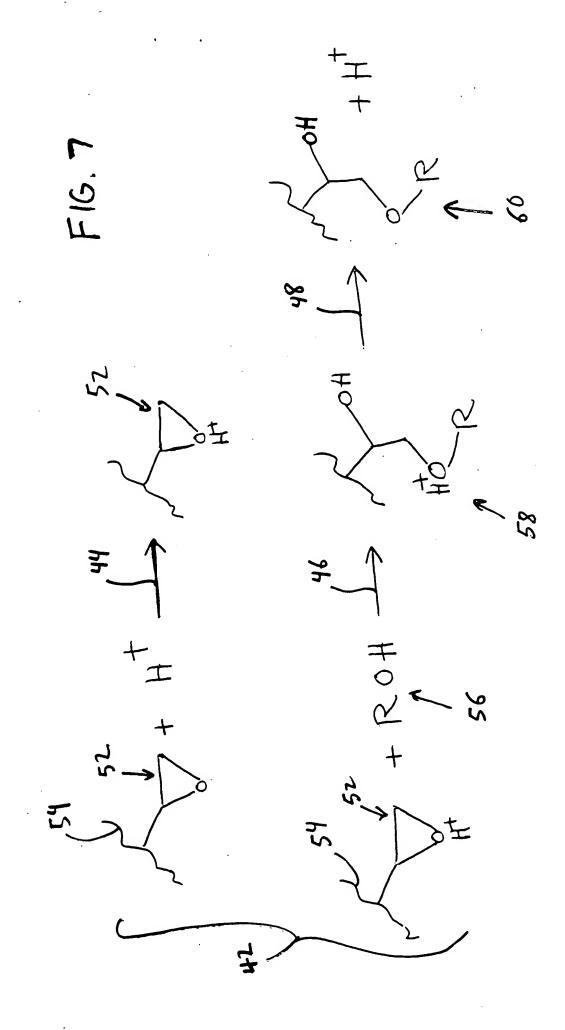
F16.48

F16.4C

F16.5A

F16.5B





Provide photo-sensitive medium
C12
Expose the medium to an intensity-pattern
under conditions that inhibit refractive index changes
-14
Contille a sign of lettel set
Segnentially expose a selected set of points and/or lines with a focal
or points and/or lines with a Tocal
region of a converging light beam
72
V
Heat the exposed medium to
favorize polymerization of oligoners therein
C16
Wash the grand madium to remove
10 1 172 001 00 110 1
unpolymerized oligomers
C18
Dry the washed medium under conditions that limit internal stresses
conditions that limit internal stresses
20
70 F16. 9

Form a 3D polymer crystalline temp	slate
L82	
Fill holes in the template with a he refractive index filler material	igh
84	
Burn or etch away the polymer stalling template from the block	cry-
C86	
80 F16	9

